

AMENDMENTS TO THE SPECIFICATION

Please replace the paragraph beginning on page 11, paragraph [00042], with the following amended paragraph:

[00042] ~~The elements comprise~~The sensor arrangement comprises a number of sensors 2 (or “sensor arrays” or “sensor elements”), processing electronics (e.g. a processing circuit, such as an array of logic elements configured to execute a series of operations) 4 receiving the output signals of the sensors 2, and a memory 6 connected to the processing circuit 4. The memory 6 may comprise a non-volatile part for storing operational instructions for the processing circuit 4, and a volatile or non-volatile part for storing measurement data. Furthermore, an input/output unit (e.g. an interface circuit) 8 is present which is connected to the processing circuit 4, and a power supply unit 9. The input/output unit 8 can transfer data from the sensor arrangement 10 to an external device, and the power supply unit 9 provides operating power to the elements on the sensor arrangement 10.

Please replace the paragraph beginning on page 13, paragraph [00049], with the following amended paragraph:

[00049] Alternatively, ~~also~~ the light intensity over the field (e.g. illumination uniformity at wafer level) can also be measured ~~too~~ (e.g. to provide a spot sensor functionality). Also, stray light ~~effect effects~~ can be measured.

Please replace the paragraph beginning on page 16, paragraph [00060], with the following amended paragraph:

[00060] The combination of test mask 13 and sensor 2 can also be provided with other optical features, in order to be able to measure various types of aberrations. The array of δ -type of objects (holes 15) is suitable for measuring the projection lens aberration. A Fresnel zone lens as test mask 13 allows detecting condenser lens aberrations. Large squares on the test mask 13 ~~allows~~ allow measurement of stray light characteristics. Regular device patterns (normal production masks MA) allow measurement of pattern fidelity and to optimize illumination conditions. A brick wall structure on the test mask 13 allows measuring other aberrations.